SECOND ALLIED COURSE II - PATTERN MAKING AND GRADING

Unit I: Fabric preparation & layout planning:

<u>Fabric preparation :</u> Preparing the fabric for cutting, Importance of grain in fabric cutting and garment construction. Methods of straightening fabric grains.

<u>Lay planning</u> Introduction, Rule to remember in pattern layout. Types of layout. Transferring pattern markings, stay stitching, ease stitching.

Unit II: Drafting and Draping:

<u>Drafting</u>: Preparation of paper patterns. Advantages of paper pattern. Pattern drafting with personal measurement. Principles for pattern drafting. Preparing draft for basic bodice, sleeve and skirt pattern.

<u>Draping</u>: Definition, types of dress form, preparation of adhesive paper dress form, Draping technique. Draping basic blocks (bodice, sleeve & skirts.).

Unit III: Flat pattern Techniques:

Definition, Pivot method, Slash & spread method, measurement method. Creating styles through dart manipulation and relocation of dart.

Unit IV: Commercial pattern and pattern grading:

<u>Commercial pattern:</u> Definition, merits and demerits, Development of commercial pattern.

<u>Pattern Grading</u>: Definition, Grading terminology, selecting a grading system, grading techniques, their advantages and disadvantages. Computer grading.Grading procedures. Grading of basic block using draft grading systems.

Unit V: Pattern alteration, Garment fitting and assembling.

<u>Pattern alteration:</u> Methods of identifying pattern alteration. General principles for pattern alteration. Common pattern alteration in a fitted bodice pattern. <u>Garment fitting and Assembling:</u> Standards for a good fit, checking for good fit, solving fitting problems and remedies.

References:

- 1. Amaden Gewford, Fairchild Fashion Draping, Connje publication, Inc 2005.
- 2. Hilary Campbell, Designing Patterns, Om Book services, New Delhi, 2003.
- 3. Helen Joseph-Pattern Making for Fashion Design, Armstrong Pearson Education, Delhi, 2000.
- 4. Sandra Betzina, Fast Fit, the Taunton press, Inc New York London, 2003.